

**NEGATIVE TYPE FLUORINE-CONTAINING RESIST COMPOSITION**

**Patent number:** JP2002090996  
**Publication date:** 2002-03-27  
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**Classification:**  
**- international:** G03F7/038; C08F214/18; C08K5/00; C08K5/16; C08L27/12; C08L29/10; G03F7/004; H01L21/027  
**- european:**  
**Application number:** JP20000281167 20000918  
**Priority number(s):**

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**Abstract of JP2002090996**

**PROBLEM TO BE SOLVED:** To provide a negative type resist composition excellent in transparency particularly to radiation and dry etching resistance as a chemical amplification type resist and giving a resist pattern excellent in sensitivity, resolution, flatness, heat resistance, etc.  
**SOLUTION:** The negative type fluorine-containing resist composition contains a fluoropolymer (X) having a monomer unit containing an acidic hydroxyl group as a constitutional unit, an acid generating compound (Y) which generates an acid when irradiated with light, an aminoplast (Z) and an organic solvent (D).

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